version, except that marked up versions are not being supplied for any added claim or canceled claim.

Claims 1-10 (Previously Canceled).

11. (Previously Amended) The method of claim 15, wherein the forming of the plurality of field emitters comprises etching material of the substrate to form the field emitters.

12. (Previously Amended) The method of claim 15, wherein the emitters are arranged into more than two demarcated, independently-addressable regions of emitters.

13. (Previously Amended) The method of claim 15, wherein the emitters are arranged into more than three demarcated, independently-addressable regions of emitters.

14. (Previously Amended) The method of claim 15, wherein the emitters are arranged into four demarcated, independently-addressable regions of emitters.

15. (Previously Amended) A method of forming a base plate for a field emission display (FED) device comprising:

providing a substrate configurable into a base plate for a field emission display (FED);

forming a plurality field emitters from material of the substrate, the emitters being arranged into more than one demarcated, independently-addressable region of emitters; and

providing address circuitry operably coupled with the field emitters and configured to independently address individual regions of the emitters, wherein the arrangement of emitters defines a plurality of rows and columns within each region, and the providing of the address circuitry comprises providing at least two separate row drivers for addressing rows in different regions of the emitters.

16. (Twice Amended) A method of forming a base plate for a field emission display (FED) device comprising:

providing a substrate configurable into a base plate for a field emission display (FED);

forming a plurality field emitters from material of the substrate, the emitters being arranged into more than one demarcated, independently-addressable region of emitters; and

providing address circuitry operably coupled with the field emitters and configured to independently address individual regions of the emitters, wherein the arrangement of emitters defines a plurality of rows and columns within each region, and the providing of the address circuitry comprises providing at least two separate column drivers for addressing columns in different regions of the emitters, and wherein demarcation of individual regions of the emitters is achieved by forming address lines that are effectively contained within the individual respective regions of the emitters.

17. (Twice Amended) A method of forming a base plate for a field emission display (FED) device comprising:

providing a monolithic substrate configurable into a base plate for a field emission display (FED);

forming a plurality field emitters from material of the monolithic substrate, the emitters being arranged into more than one demarcated, independently-addressable region of emitters; and

providing address circuitry operably coupled with the field emitters and configured to independently address individual regions of the emitters, wherein the arrangement of emitters defines a plurality of rows and columns within each region, and the providing of the address circuitry comprises providing at least two separate row drivers and at least two separate column drivers for addressing rows and columns in different respective regions of the emitters, and wherein demarcation of individual regions of the emitters is achieved by forming address lines that are effectively contained within the individual respective regions of the emitters.

18. (Original) A method of forming a base plate for a field emission display (FED) device comprising:

providing a monolithic addressable matrix of rows and columns of field emitters, the matrix having a perimetral edge defining length and width dimensions of the matrix;

partitioning the matrix into a plurality of discretely-addressable sub-matrices of field emitters; and

providing row and column address lines operably coupled with the matrix and collectively configured to address the field emitters, at least one of the row or column address lines having a length within the matrix which is sufficient to address less than all of the field emitters which lie in the direction along which the at least one row or column address line extends within the matrix.

19. (Original) The method of claim 18, wherein the length of said one row or column address line within the matrix is less than a length or width dimension of the matrix.

20. (Original) The method of claim 18, wherein the length of said one row or column address line within the matrix is less than a length or width dimension of one of the sub-matrices.

21. (Original) The method of claim 18, wherein the partitioning of the matrix comprises partitioning said matrix into more than two sub-matrices.

22. (Original) The method of claim 18, wherein the partitioning of the matrix comprises partitioning said matrix into more than three sub-matrices.

23. (Original) The method of claim 18, wherein the partitioning of the matrix comprises partitioning said matrix into four sub-matrices.

24. (Previously Amended) A method of forming a field emission display (FED) device comprising:

providing a substrate configurable into a base plate for a field emission display (FED);

forming a plurality of discrete, segmented regions of field emitter tips by removing at least portions of the substrate; individual discrete, segmented regions being electrically isolated into separately-addressable regions of field emitter tips;

providing a face plate supporting areas of luminescent material; and

mounting the face plate in operable proximity with the substrate.

25. (Original) The method of claim 24, wherein the forming of the plurality of discrete, segmented regions comprises forming at least two regions.

26. (Original) The method of claim 24, wherein the forming of the plurality of discrete, segmented regions comprises forming at least three regions.

27. (Original) The method of claim 24, wherein the forming of the plurality of discrete, segmented regions comprises forming at least four regions.

Claims 28-31 (Previously Canceled).

32. (Original) A method of forming a field emission display (FED) device comprising:

providing a monolithic addressable matrix of rows and columns of field emitters, the matrix having a perimetral edge defining length and width dimensions of the matrix;

partitioning the matrix into a plurality of discretely-addressable sub-matrices of field emitters;

providing row and column address lines operably coupled with the matrix and collectively configured to address the field emitters, at least one of the row or column address lines having a length within the matrix which is sufficient to address less than all of the field emitters which lie in the direction along which the at least one row or column address line extends within the matrix;

providing a face plate supporting areas of luminescent material; and

mounting the face plate in operable proximity with the monolithic addressable matrix.

Claims 33-40 (Previously Canceled).

41. (Amended) A field emission display (FED) device comprising:

a monolithic addressable matrix of rows and columns of field emitters, the matrix having a perimetral edge defining length and width dimensions of the matrix; the matrix being partitioned into a plurality of discretely-addressable sub-matrices of field emitters, wherein partitioning of the matrix is performed by forming address lines that are effectively contained within the respective sub-matrices of field emitters;

row and column address lines operably coupled with the matrix and collectively configured to address the field emitters, at least one of the row or column address lines having a length within the matrix which is sufficient to address less than all of the field emitters which lie in the direction along which the at least one row or column address line extends within the matrix; and

a face plate supporting areas of luminescent material mounted in operable proximity with the monolithic addressable matrix.

42. (Original) The field emission display (FED) device of claim 41, wherein the matrix comprises more than two sub-matrices.

43. (Original) The field emission display (FED) device of claim 41, wherein the matrix comprises more than three sub-matrices.

44. (Original) The field emission display (FED) device of claim 41, wherein the matrix comprises four sub-matrices.

45. (Twice Amended) A method of forming a base plate for a field emission display (FED) device comprising:

providing a monolithic substrate configurable into a base plate for a field emission display (FED);

forming a plurality of discrete, segmented regions of field emitter tips by removing at least portions of the substrate to provide a monolithic addressable matrix of rows and columns of field emitters, the matrix having a perimetral edge defining length and width dimensions of the matrix; the matrix being partitioned into a plurality of separately-addressable sub-matrices of field emitters, and wherein partitioning of the matrix is performed by forming address lines that are effectively contained within the respective sub-matrices of field emitters;

row and column address lines operably coupled with the matrix and collectively configured to address the field emitters, at least one of the row or column address lines having a length within the matrix which is sufficient to address less than all of the field emitters which lie in the direction along which the at least one row or column address line extends within the matrix; and

a face plate supporting areas of luminescent material mounted in operable proximity with the monolithic addressable matrix.

46. (Previously Added) The field emission display (FED) device of claim 45, wherein the matrix comprises more than two sub-matrices.

47. (Previously Added) The field emission display (FED) device of claim 45, wherein the matrix comprises more than three sub-matrices.

Please add the following new claims:

48. (New) The method of claim 15, wherein the independently addressable regions of emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the emitters.

49. (New) The method of claim 48, wherein the independently addressable regions are formed by modifying the photomask such that subsequently-etched row and column lines are contained within individual respective regions of emitters without extending into other individual regions.

50. (New) The method of claim 16, wherein the independently addressable regions of emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the emitters.

51. (New) The method of claim 50, wherein the independently addressable regions are formed by modifying the photomask such that subsequently-etched row and column lines are contained within individual respective regions of emitters without extending into other individual regions.

52. (New) The method of claim 17, wherein the independently addressable regions of emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the emitters.

53. (New) The method of claim 52, wherein the independently addressable regions are formed by modifying the photomask such that subsequently-etched row and column lines are contained within individual respective regions of emitters without extending into other individual regions.

54. (New) The method of claim 18, wherein the independently addressable regions of emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the emitters.

55. (New) The method of claim 54, wherein the independently addressable regions are formed by modifying the photomask such that subsequently-etched row and column lines are contained within individual respective regions of emitters without extending into other individual regions.

56. (New) The method of claim 24, wherein the segmented regions are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the emitters.

57. (New) The method of claim 24, wherein the segmented regions are formed by modifying a photomask such that subsequently-etched row and column lines are contained within individual respective regions of emitters without extending into other individual regions.

58. (New) The method of claim 32, wherein the discretely addressable sub-matrices of field emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable sub-matrices of the field emitters.

59. (New) The method of claim 58, wherein the discretely addressable regions of field emitters are formed by modifying a photomask such that subsequently-etched row and column lines are contained within individual respective sub-matrices of field emitters without extending into other sub-matrices.

60. (New) The field emission display of claim 41, wherein the discretely addressable sub-matrices of field emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable regions of the field emitters.

61. (New) The field emission display of claim 41, wherein the discretely addressable regions of field emitters are formed by modifying a photomask such that subsequently-etched row and column lines are contained within individual respective regions of field emitters without extending into other individual regions.

62. (New) The method of claim 45, wherein the separately addressable sub-matrices of field emitters are formed by configuring a photomask such that subsequently-etched row and column lines extend across a matrix that corresponds only to the addressable sub-matrices of the field emitters without extending into other individual sub-matrices.